

# Save Time. Improve your Yields.

WaferSense® & ReticleSense® - The world's most efficient and effective wireless measurement devices.



Leveling



Vibration



Humidity



Particle



Gapping



Teaching



Resistance



**Proven &  
Adopted by  
FABs & OEMs  
Worldwide**

# WaferSense® and ReticleSense® Wireless Measurement Devices

When you need the most efficient and effective measurement devices for semiconductor tool set-up and maintenance processes, count on CyberOptics, the global market leader in wireless semiconductor measurement devices for chamber gapping, leveling, wafer handoff teaching, vibration, airborne particle, relative humidity and resistance measurement.

## Proven and Adopted

Major semiconductor fabs and equipment OEMs worldwide have **adopted** CyberOptics wireless measurement devices. Several OEM standards require the use of the WaferSense and ReticleSense devices which have been **adopted as the BKM (Best Known Method)** due to the increased level of precision required with today's ever smaller chip geometries.

## Most Efficient and Effective

- Since the wireless, battery powered devices are wafer or reticle shaped, they can generally travel anywhere a wafer or reticle travels, providing optimal ease-of-use and access to locations that otherwise may be difficult or impossible to reach.
- Calibrations can be done under closed-chamber process conditions with the vacuum compatible devices.
- Count on accurate, precise, reliable and repeatable results that save time and expense compared to traditional or legacy methods.

## Save Time and Expense

- ✓ Improve yields and increase tool uptime
- ✓ Increase throughput
- ✓ Reduce resource needs
- ✓ Speed equipment set-up, maintenance cycles, trouble-shooting, qualification and release to production
- ✓ Speed tool optimization, stabilization and standardization
- ✓ Streamline fab processes
- ✓ Establish repeatable and verifiable standards

## Real-Time Data with CyberSpectrum™ Software

NEW!

- CyberSpectrum offers multi-application functionality with the WaferSense and ReticleSense lines of devices, while also providing control to run multiple devices simultaneously.
- Receive and record data in real-time on your laptop with this easy-to-use software that includes multi-touch controls.
- Compare past and present data as well as one tool to another easier and faster without opening an additional application with Review functionality integrated into CyberSpectrum.



CYBERSPECTRUM



# WaferSense® Portfolio

Available in 150mm, 200mm and 300mm sizes\*



## Auto Resistance Sensor™

- Shorten equipment maintenance cycles with wafer-like 4-wire resistance sensor.
- Predict when a tool needs maintenance with quantitative analysis of measured mean resistance over time.
- Improve cell-to-cell process uniformity with objective and repeatable resistance measurement.

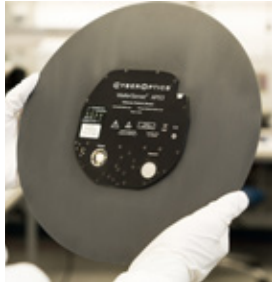
**NEW!**



## Auto Vibration & Leveling Sensor™

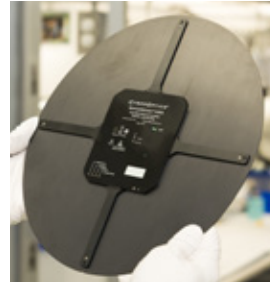
- Speed real-time vibration and leveling measurements.
- Speed equipment qualification and shorten equipment maintenance cycles,
- Laminated GHC (chemically hardened glass) substrate.

**NEW!**



## Airborne Particle Sensor™

- Quickly monitors, identifies and enables troubleshooting of airborne particles down to 0.14µm within semiconductor process equipment.
- Easily identifies when and where the particles originate and measures the effectiveness of cleaning adjustments and repairs in real-time.
- Carbon fiber composite substrate.



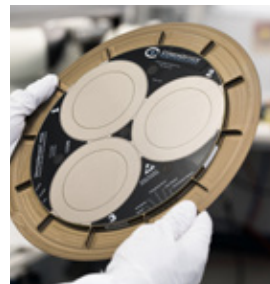
## Auto Multi Sensor™

- Speeds measuring leveling, vibration and humidity with a thinner, lighter, all-in-one multi sensor.
- Monitors humidity when wafers are in the FOUP awaiting next process step to prevent yield loss.
- Carbon fiber composite substrate.



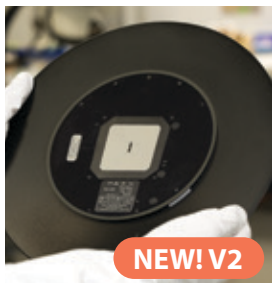
## Auto Leveling System™

- Speeds setting the right inclination by measuring pitch, roll, rise over run and vertical inclinations.
- Quickly and accurately enables setting the same level across the tools for better process uniformity.
- Carbon fiber composite substrate.



## Auto Gapping System™

- Speeds non-contact gap measurements and parallelism adjustments under vacuum for semiconductor processes such as thin-film deposition, sputtering and etch.
- Improves uniformity, tool availability and repeatability.
- Anodized aluminum housing.



## Auto Teaching System™

- “Sees” inside equipment to capture three dimensional offset data (x, y, and z) to quickly teach wafer transfer positions.
- Lowers particulate contamination with accurate wafer hand-off calibration, proper alignment and set ups.
- Travels through more locations with thinner form factor.
- Chemically hardened glass (CHG).

**NEW! V2**



## Auto Vibration System™

- Monitors 3-axis accelerations and vibration to maximizing acceleration and minimize vibration.
- Records data to enable comparison between past and present, as well as one tool to another, to reduce particles, maintenance time and cycle time.
- Carbon fiber composite substrate.

# ReticleSense® Portfolio

Available in 6 inch reticle form factor



## Airborne Particle Sensor

- Quickly monitors, identifies and enables troubleshooting of airborne particles down to 0.14µm within semiconductor process equipment and automated material handling systems.
- Glass filled PEEK housing (APSR) and Quartz surface housing (APSRQ) available.



## Auto Multi Sensor

- Speed leveling, vibration and humidity measurements with all-in-one multi sensor.
- Monitors humidity when reticles are in the stocker awaiting next process step to prevent yield loss.
- Quartz surface housing.



## Auto Teaching System™

- “Sees” inside equipment to capture three dimensional offset data (x, y, and z) to quickly teach reticle transfer positions.
- Lowers particulate contamination with accurate reticle hand-off calibration, proper alignment and set ups.

**NEW!**



# APS Technology

## Did You Know?

The APS technology enables equipment engineers to shorten equipment qualification, release to production and maintenance cycles, all while reducing expenses. Customers have experiences up to **88% time savings**, up to **95% reduction in costs** and up to **20X the throughput** with half the manpower requirements by using the APS technology relative to legacy surface scan wafers.



**Save Time**

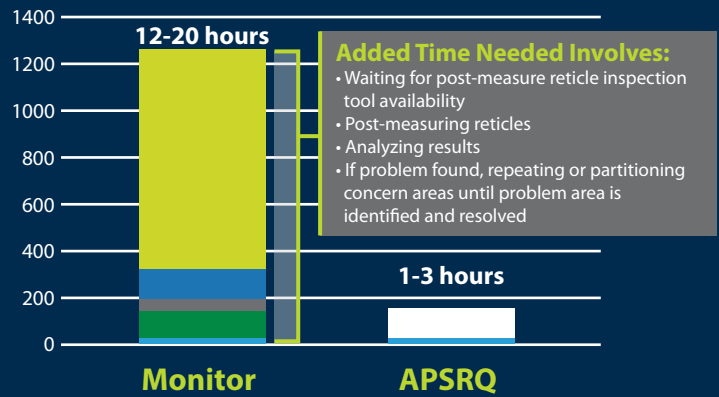


**Save Expense**



**Increase Throughput**

## Reticle Monitor vs. ReticleSense® APSRQ Time Comparison: 10x Time Savings



Deploy WaferSense and ReticleSense measurement devices for chamber gapping, leveling, wafer hand-off teaching, vibration, airborne particle, relative humidity and resistance measurement in your applications. Visit our website for additional application information.

### AVS



### AMS\*



### Applications

- Epitaxy
- Thermal oxidation/metallization
- Plasma vapor deposition; PVD
- Chemical vapor deposition; CVD, ALD
- CMP
- Atomic layer deposition; ALD
- Photo lithography
- Wet (chemical) etch, plasma etch
- Dry etch
- Ion implant
- Diffusion/furnace
- Rapid thermal anneal; RTA, RTP
- Test and inspection
- Metrology
- Micro contamination
- Auto handling system; AMHS
- Module repair

### ALS



### AVLS3



### AGS



### Applications

- Chemical vapor deposition; CVD, ALD
- Atomic layer deposition; ALD
- Wet (chemical) etch, plasma etch

### APS3\*



### Applications

- Factory interface FI/EFEM
- Photo Lithography
- Diffusion/Furnace
- Test and Inspection
- Rapid Thermal Anneal; RTA, RTP
- Metrology
- Microcontamination
- Auto Handling System; AMHS and Stockers

### ATS2\*



### Applications

- Plasma vapor deposition; PVD
- Chemical vapor deposition; CVD, ALD
- Photo lithography
- Wet (chemical) etch, plasma etch
- Dry etch
- Ion implant
- Automated handling system

### NEW! V2

### ARS



### Applications

- Electrochemical Deposition; ECD

\*Available in reticle form factor